MMI-based polarization beam splitter/combiner for InP photonic integrated circuits

Felicetti, M.; Kojima, K.; Koike-Akino, T.; Wang, B.; Parsons, K.; Nishikawa, S.; Yagyu, E. TR2015-052 July 2015

Abstract

An MMI-based polarization splitter/combiner with a TE-TM splitting ratio above 15 dB over a 21 nm wavelength range is demonstrated. The compact device is integrated in a photonic circuit within an InP multi-project wafer run.

2015 Integrated Photonics Research, Silicon and Nano Photonics (IPR)

This work may not be copied or reproduced in whole or in part for any commercial purpose. Permission to copy in whole or in part without payment of fee is granted for nonprofit educational and research purposes provided that all such whole or partial copies include the following: a notice that such copying is by permission of Mitsubishi Electric Research Laboratories, Inc.; an acknowledgment of the authors and individual contributions to the work; and all applicable portions of the copyright notice. Copying, reproduction, or republishing for any other purpose shall require a license with payment of fee to Mitsubishi Electric Research Laboratories, Inc. All rights reserved.

Copyright © Mitsubishi Electric Research Laboratories, Inc., 2015 201 Broadway, Cambridge, Massachusetts 02139

MMI-based polarization beam splitter/combiner for InP photonic integrated circuits

Manuela Felicetti^{1,2}, Keisuke Kojima¹, Toshiaki Koike-Akino¹, Bingnan Wang¹, Kieran Parsons¹, Satoshi Nishikawa³, and Eiji Yagyu³

 ¹ Mitsubishi Electric Research Laboratories (MERL), 201 Broadway, Cambridge, MA 02139, USA
² Department of Electrical Engineering, Eindhoven University of Technology, Eindhoven, The Netherlands
³ Advanced Technology R&D Ctr., Mitsubishi Electric Corp., 8-1-1 Tsukaguchi-Honmachi, Amagasaki, Hyogo, Japan kojima@merl.com

Abstract: An MMI-based polarization splitter/combiner with a TE-TM splitting ratio above 15 dB over a 21 nm wavelength range is demonstrated. The compact device is integrated in a photonic circuit within an InP multi-project wafer run.

OCIS codes: 230.3120 Integrated optics devices; 130.5440 Polarization-selective devices; 060.2340 Fiber optics components.

1. Introduction

Modern telecommunication networks are evolving to support high speed services, which require polarization handling. The orthogonal polarizations TE and TM can be used to double the capacity of the optical transmission system through polarization diversity. This functions can be achieved thanks to a device capable of splitting and combining the polarization states of light. Ultra short polarization beam splitters (PBS) based on directional mode couplers [1–4] or multi-mode interferometer (MMI) [5] have been designed in silicon technology. However, a PBS device in indium phosphide (InP) substrate is also required since it can be integrated with active components, i.e. lasers, modulators, and photo-detectors. A number of InP PBS with different structures have been reported, e.g. directional couplers [6], MMI [7], Mach-Zehnder interferometer with polarization converter [8]. The drawback is that the InGaAsP-InP layer stack has a lower index contrast compared to Silicon-On-Insulator (SOI), leading to a weak birefringence between TE and TM polarized modes. Thus, the TE-TM coupling length is longer in InP PBS devices than silicon ones, resulting in less compact devices. The shortest device device reported is 600 μ m with a splitting ratio (SR) of 10 dB [8]. In this paper, a 370 μ m MMI-based polarization splitter is demonstrated. The TE and TE beating lengths ensure the splitting of the two modes at the device output ports. The PBS is fabricated by SMART Photonics B.V. within an InGaAsP-InP multi-project wafer (MPW) run [9].

2. Design and simulations

The PBS device (Fig.1(a)) consists of a single mode input waveguide ($W_{wg} = 1.5 \ \mu$ m), a short tapered section ($L_{gap} = 36 \ \mu$ m) for a smooth mode transition, an MMI section ($W_{MMI} = 2.5 \ \mu$ m and $L_{MMI} = 370 \ \mu$ m) and two output ports (port_{1,2} = W_{wg}). The input/output ports and the MMI section are fabricated in deeply etched trenches. The MMI section presents a shallow etched gap of 0.5 μ m. The shallow etch depth (nominally 0.1 μ m into the core layer) is defined by the foundry, thus the gap width is the design parameter that defines the TE and TM propagation constants. Fig.1(b) shows the fundamental and first order TE and TM modes in the MMI section. Due to the different coupling length for TE and TM, the mode interference in the MMI section is such that the TE and TM input mode couple out to port 1 and port 2 respectively. Fig.1(c) shows the field propagation along the PBS device for TE or TM polarized input.

The TE and TM coupling lengths in the MMI section are defined as

$$L_{\pi_{TE}} = rac{\pi}{eta_{TE0} - eta_{TE1}}, \qquad L_{\pi_{TM}} = rac{\pi}{eta_{TM0} - eta_{TM1}}$$

where β_{TE0} and β_{TE1} are the mode propagation constant for the fundamental and first order TE modes, while β_{TM0} and β_{TM1} are the mode propagation constant for the fundamental and first order TM modes. The calculated beat lengths are 37.52 μ m for TE mode and 53.76 μ m for TM mode. To split the TE and TM modes to port 1 and port 2 respectively, the optimal MMI length is 370 μ m.



Fig. 1. (a) PBS device scheme. (b) Cross-section view of the MMI TE and TM modes. (c) TE and TM field propagation in the PBS device.

3. Measurements

The performance of the device is evaluated in terms of splitting ratio and insertion loss for both TE and TM polarized input mode. When the input mode is TE polarized, the splitting ratio is found as [8]

$$SR(TE_{in}) = 10\log\left(\frac{P_{TMout1} + P_{TEout1}}{P_{TMout2} + P_{TEout2}}\right)$$
(1)

whilst, if the input mode is TM polarized the splitting ratio (SR) can be calculated as

$$SR(TM_{in}) = 10\log\left(\frac{P_{TMout2} + P_{TEout2}}{P_{TMout1} + P_{TEout1}}\right)$$
(2)

The insertion loss is estimated with respect to the propagation loss of a single mode straight waveguide, used as a reference. The characterization of the PBS consists in determining the splitting ratio for both TE and TM input polarizations. At the input side of the PBS device, an erbium-doped fiber amplifier (EDFA) is used as a light source. The EDFA is connected to a polarization beam splitter (off chip) to define the polarization at the input coupling fiber. The polarization maintaining (PM) fiber, that couples the light into the PBS device, is rotated to launch a TE or a TM polarized mode¹. At the output side, the total power (TE+TM) is coupled one at the time from the PBS output ports to a PM fiber. The output spectra are recorded using an optical spectrum analyzer (OSA). Measurement results (Fig.2(a)) show an SR above 15 dB over a wavelength range of 36 nm (1526-1562 nm) for the TE input and 32 nm (1515-1547) for the TM input. The two wavelength ranges have an overlap region of 21 nm (1526-1547 nm). The measured PBS insertion loss (Fig.2(b)), over the TE and TM SR overlap wavelength region, is 4-5.5 dB for the TE mode and 2-4 dB for the TM mode. The discrepancy between simulation and measurements results could be explained with a deviation of the design parameters during the PBS fabrication.

¹Prior the PBS characterization, the orientation of the fiber to the TE or TM mode is performed in free space using a polarizer.



Fig. 2. (a) PBS splitting ratio (SR) and (b) insertion loss (Loss) as a function of the wavelength.

4. Conclusions

An MMI-based polarization splitter/coupler integrated in an InP photonic circuit has been designed. The compact 370 μ m device is fabricated using a standard foundry process within an MPW run. The measurement results demonstrate the good performance of the device with an SR above 15 dB over a wavelength range of 21 nm (1526-1547 nm) for both TE and TM input. In this wavelength range, the measured PBS insertion loss is 4-5.5 dB for the TE mode and 2-4 dB for the TM mode. The device performance could be further improved with a refinement in the device design and/or fabrication processes.

References

- 1. Lin, Shiyun and Hu, Juejun and Crozier, Kenneth, "Ultracompact, broadband slot waveguide polarization splitter", Applied Physics Letters, **98**, 151101 (2011).
- 2. H. Fukuda, K. Yamada, T. Tsuchizawa, T. Watanabe, H. Shinojima, and S. Itabashi, "Ultrasmall polarization splitter based on silicon wire waveguides," Opt. Express 14, 12401 (2006).
- 3. Daoxin Dai, "Silicon Polarization Beam Splitter Based on an Asymmetrical Evanescent Coupling System With Three Optical Waveguides," Lightwave Technology, Journal of , **30**, 3281 (2012).
- 4. A. Melikyan C. Gaetner, K. Koehnle, A. Muslija, M. Sommer, M. Kohl, C. Koos, W. Freude, and J. Leuthold, "Integrated wire grid polarizer and plasmonic polarization beam splitter," OFC, paper OW1E.3 (2012).
- 5. Yao-Feng Ma; Ding-wei Huang, "A Compact Silicon-on-Insulator MMI-based Polarization Splitter," IEEE/LEOS International Conference on Optical MEMS and Nanophotonics, Paper TuP34 (2007)
- Ghirardi, F.; Brandon, J.; Carre, M.; Bruno, A; Menigaux, L.; Carenco, A, "Polarization splitter based on modal birefringence in InP/InGaAsP optical waveguides," Photonics Technology Letters, 5, 1047 (1993).
- K. Kojima, W. Yuan, B. Wang, T. Koike-Akino, K. Parsons, S. Nishikawa, and E. Yagyu, "An MMI-based polarization splitter using patterned metal and tilted joint," Opt. Express 20, B371 (2012).
- L.M. Augustin, R. Hanfoug, J. J. G. M. Van der Tol, W. J. M. De Laat, M. K. Smit, "A Compact Integrated Polarization Splitter/Converter in InGaAsP-InP," Photonics Technology Letters, 19, 1286 (2007).
- 9. M. Smit et al., "An introduction to InP-based generic integration technology," Semicond. Sci. Technol., **29**, 41 (2014)